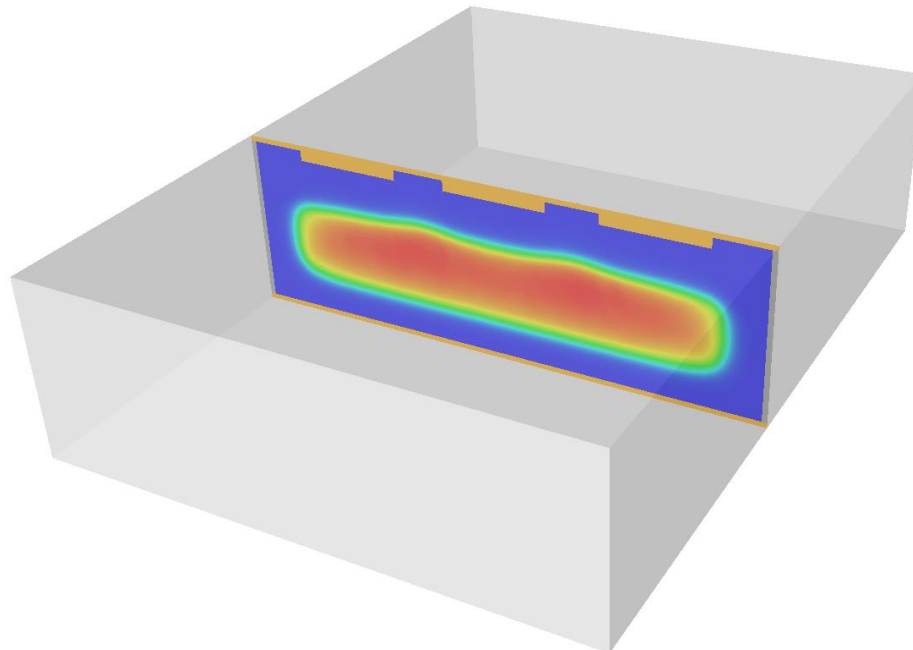


— CASE EXAMPLE —

# DLC Coating by Plasma CVD

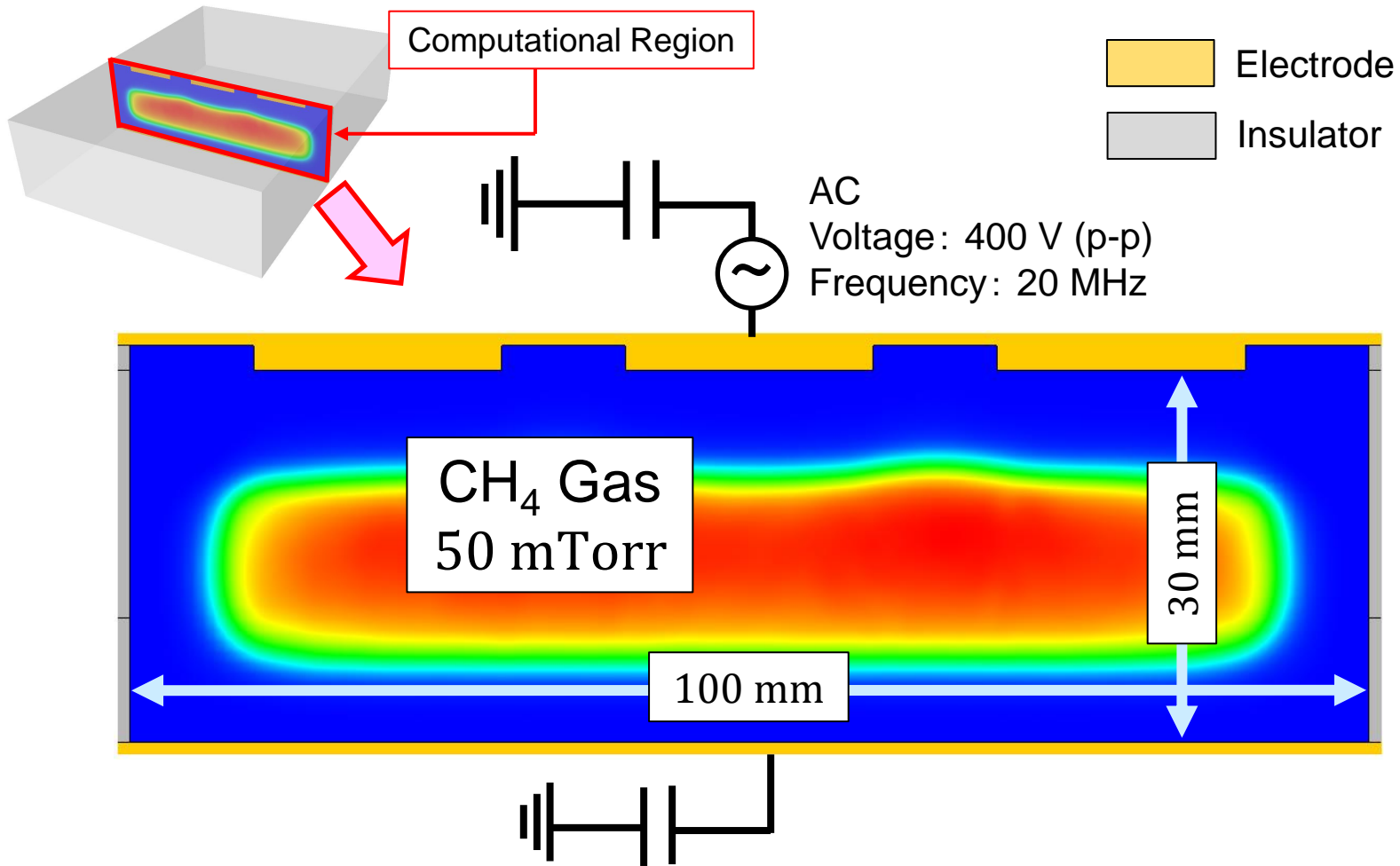
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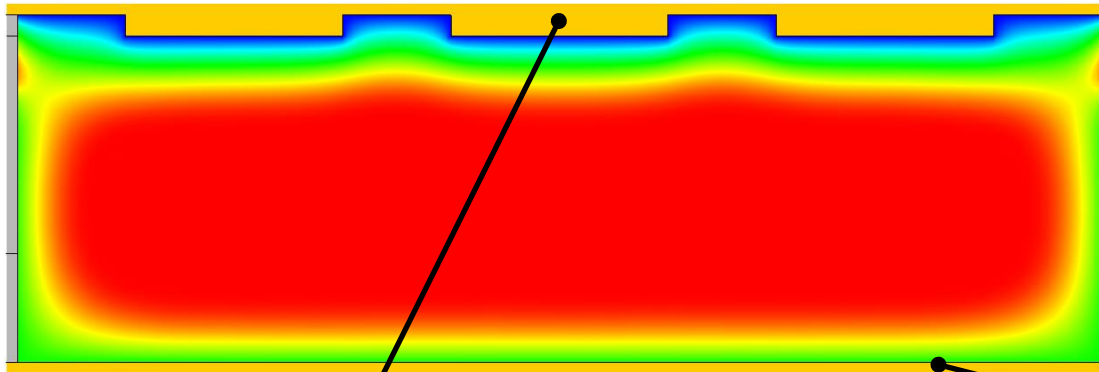
# Model

## Coating by CH<sub>4</sub> Plasma

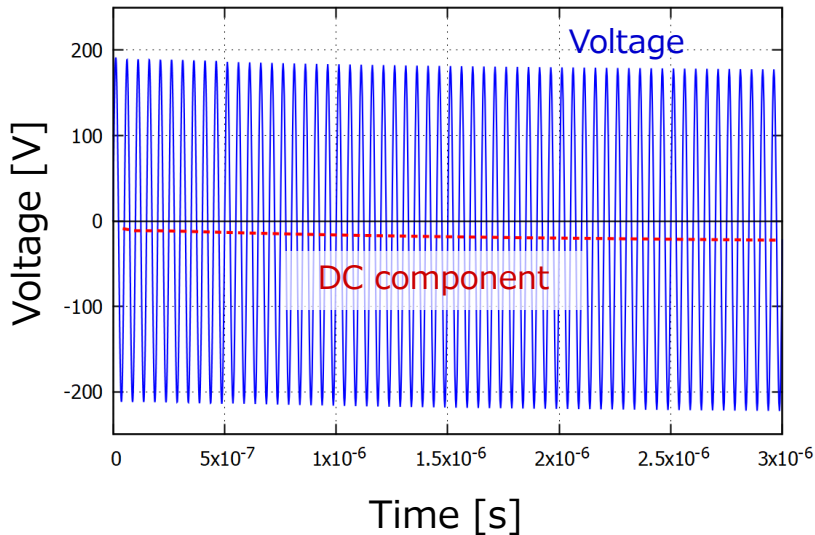
2D model



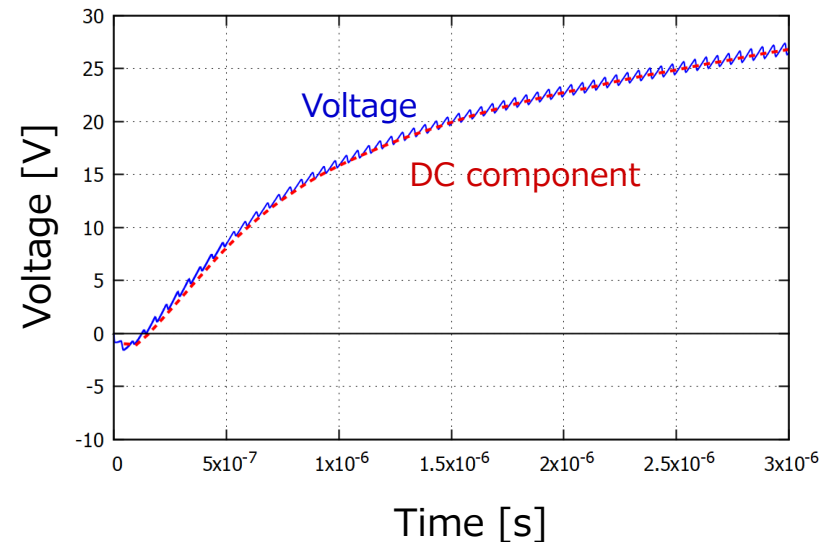
Voltage (avg.)



Time Dependence of Voltage  
Upper Electrode

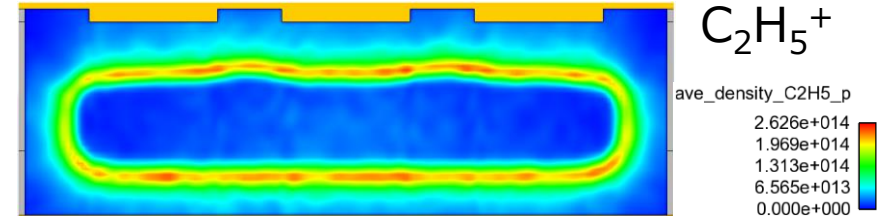
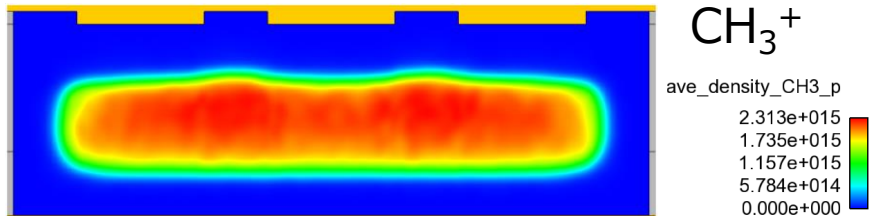
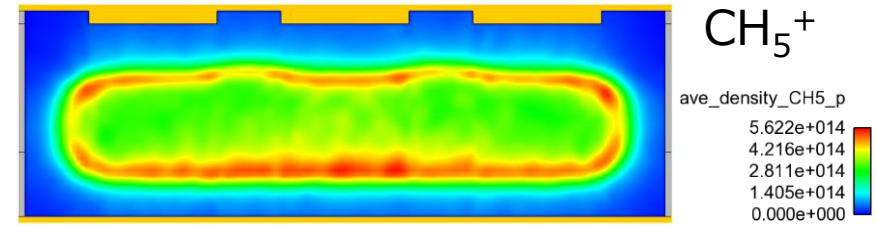
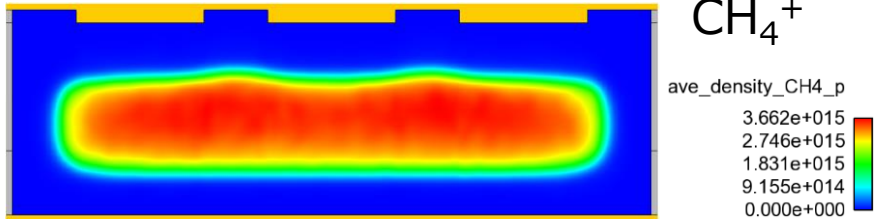
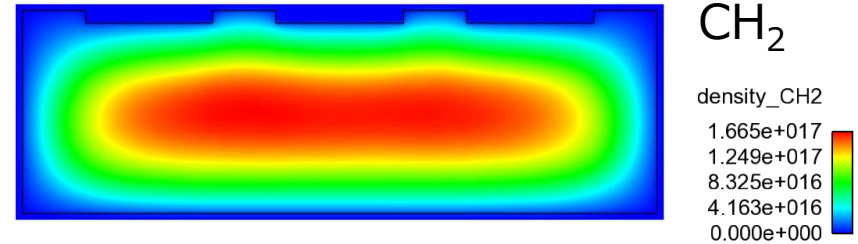
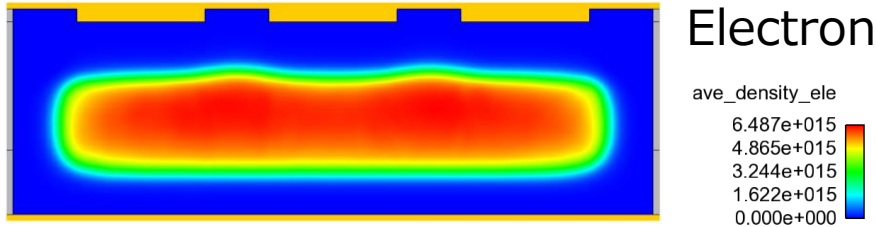
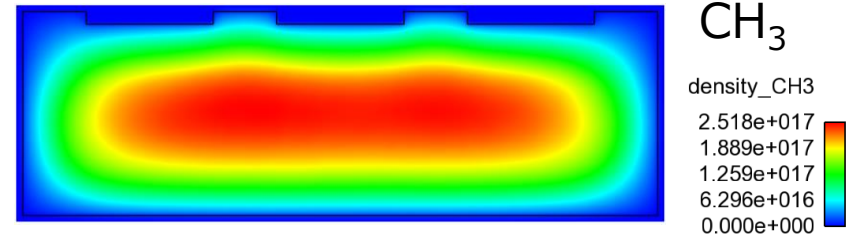


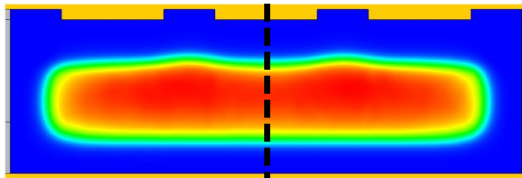
Lower Electrode



# Particle Density

The unit is  $[/math>m<sup>3</sup>]. In addition to them, CH<sub>4</sub> as a background and ions, excited species and radicals as reaction products are considered.$



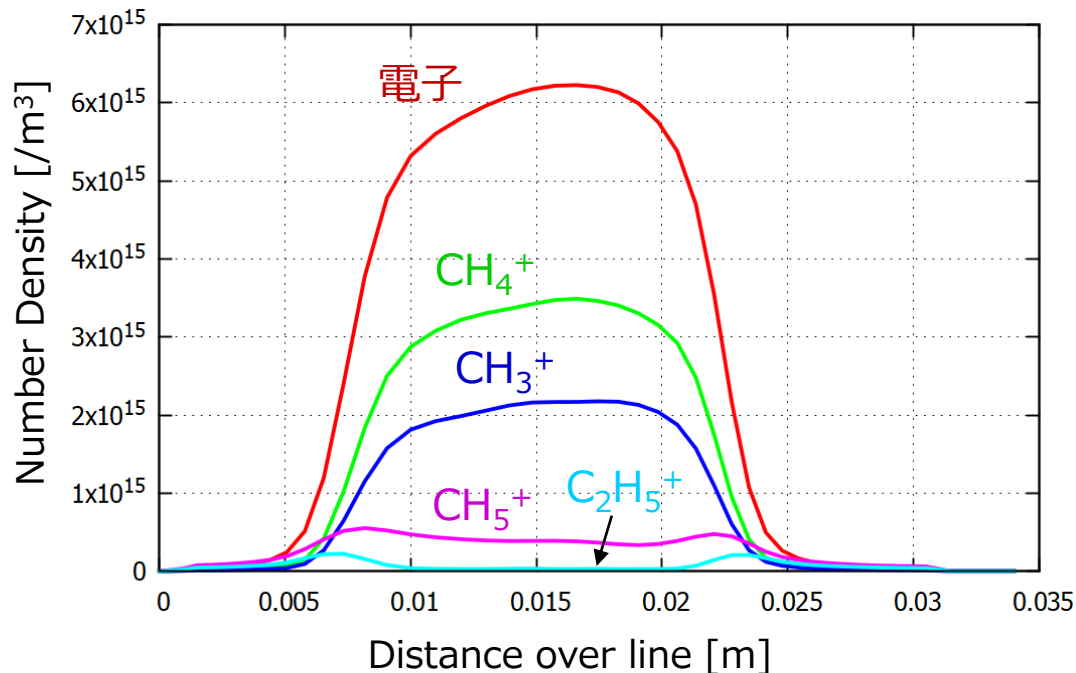


Plot over line

Main generation process of  $\text{CH}_5^+$  and  $\text{C}_2\text{H}_5^+$

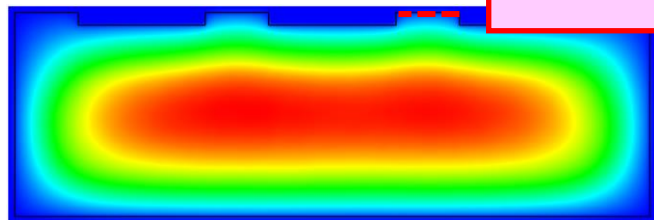
- $e + \text{CH}_4 \rightarrow e + e + \text{CH}_4^+$
- $e + \text{CH}_4 \rightarrow e + e + \text{CH}_3^+ + \text{H}$
- $\text{CH}_4^+ + \text{CH}_4 \rightarrow \text{CH}_5^+ + \text{CH}_3$
- $\text{CH}_3^+ + \text{CH}_4 \rightarrow \text{C}_2\text{H}_5^+ + \text{H}_2$

Number Density Distribution of Electron and ions (avg.)



By-products such as  $\text{CH}_5^+$  and  $\text{C}_2\text{H}_5^+$  are peaked around main products such as  $\text{CH}_4^+$  and  $\text{CH}_3^+$ .

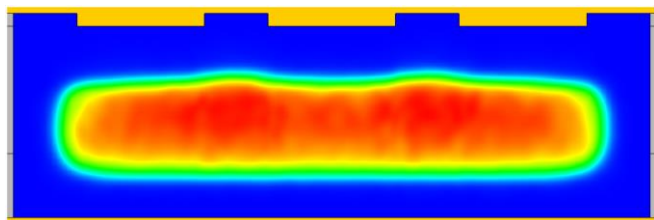
## CH<sub>3</sub> Density



density\_CH3 [ /m<sup>3</sup> ]

2.518e+017
1.889e+017
1.259e+017
6.296e+016
0.000e+000

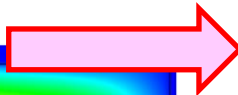
## CH<sub>3</sub><sup>+</sup> Density



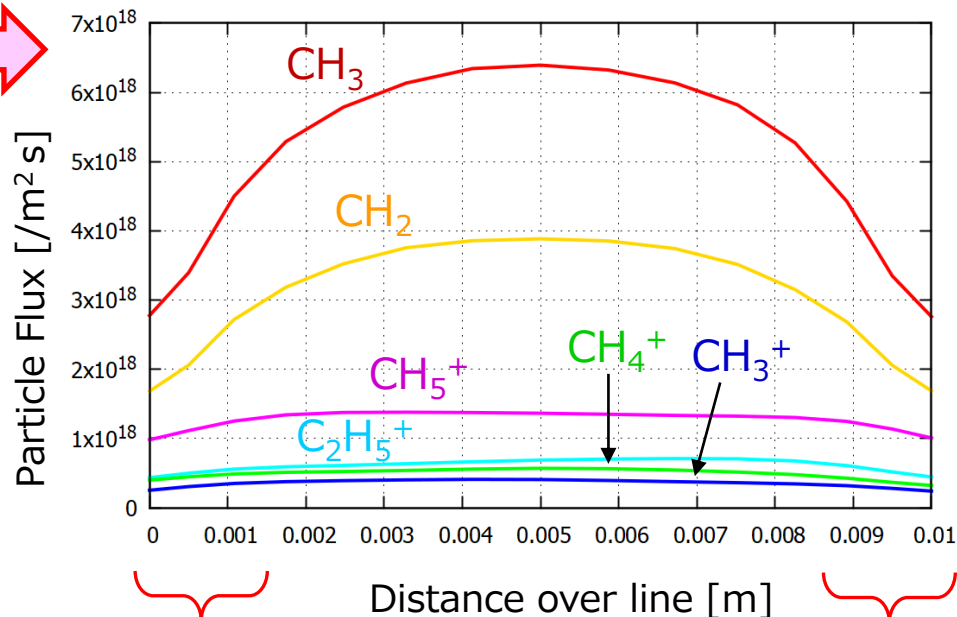
ave\_density\_CH3\_p [ /m<sup>3</sup> ]

2.313e+015
1.735e+015
1.157e+015
5.784e+014
0.000e+000

Plot over line

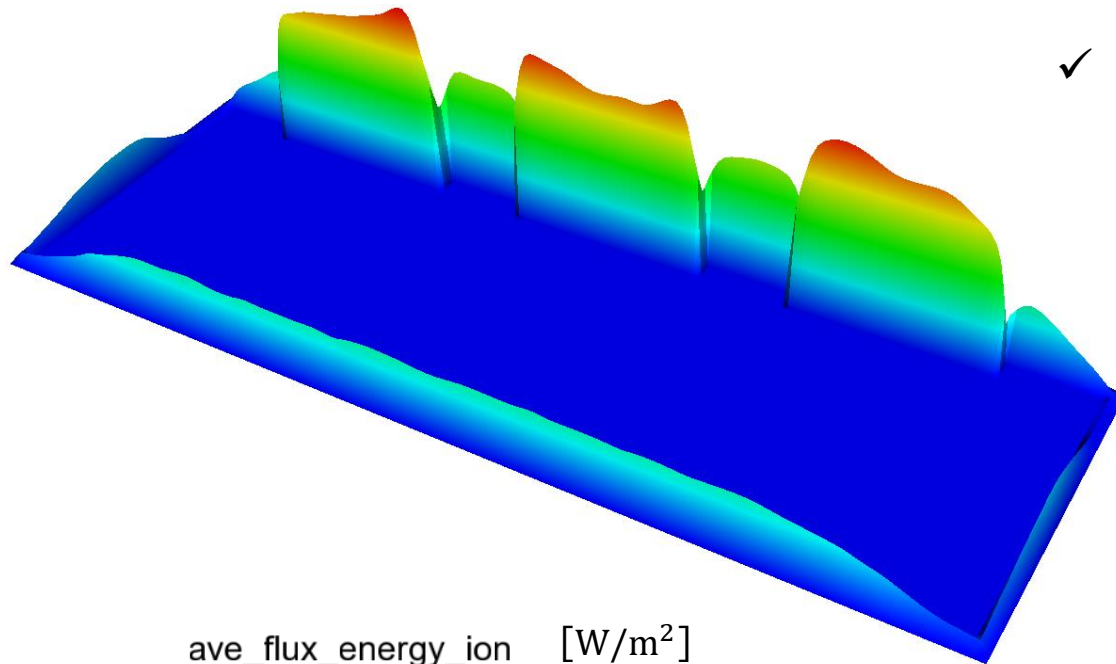


## Surface Flux of Ions and Radicals (avg.)



- ✓ Ions have relatively low flux on retracted position due to higher directivity of them than neutral radicals.

Ion Energy Flux on surface (avg.)



✓ Ion energy flux, which is useful to estimate an ion assist, is also evaluated.

ave\_flux\_energy\_ion [W/m<sup>2</sup>]

